

REMARKS

By the present amendment and response, independent claim 1 and dependent claims 3 and 5-10 have been amended to overcome the Examiner's objections. Claims 23 and 24 have been canceled. As a result of the above amendments, no new claim language requiring a search or further consideration has been introduced. Thus, claims 1-10, 21-22, and 25-30 remain pending in the present application. Reconsideration and allowance of pending claims 1-10, 21-22, and 25-30 in view of the following remarks are requested.

In the Office Action dated September 16, 2003, the Examiner has *finally rejected* claims 1-10, 21-22, 24-28, and 30 on the basis of new ground(s) of rejection. Applicant respectfully requests reconsideration and withdrawal of the finality of the rejection of the Office Action dated September 16, 2003.

The Examiner has rejected claims 1-10 under 35 USC §112, second paragraph. Applicant has amended claims 1, 3, and 5-10 in response to the Examiner's objection and submits that the requirements of 35 USC §112, second paragraph, have been met.

The Examiner has further rejected claim 23 under 35 USC §112, second paragraph. Applicant has canceled claim 23.

The Examiner has further rejected claims 1-10, 21, 22, 24-28, and 30 under 35 USC §103(a) as being unpatentable over U.S. patent application publication number 2002/0127847 to Alling et al. ("Alling") in combination with U.S. patent number 6,398,926 B1 to Lotar Peter Mahneke ("Mahneke"), U.S. patent number 3,706,635 to Xavier Kowalski ("Kowalski"), and U.S. patent number 6,486,533 B2 to Krishnamoorthy

et al. ("Krishnamoorthy"). For the reasons discussed below, Applicant respectfully submits that the present invention, as defined by amended independent claim 1, is patentably distinguishable over Alling, Mahneke, Kowalski, and Krishnamoorthy, singly or in any combination thereof.

The present invention, as defined by amended independent claim 1, teaches, among other things, electroplating a copper (Cu) surface in a chemical solution, thereby forming a copper-zinc (Cu-Zn) alloy film on the Cu surface, "wherein the Cu-Zn alloy film has a zinc (Zn) content in a concentration range of approximately 0.10 atomic % to approximately 1.0 atomic %." As disclosed in the present application, the present invention's Cu-Zn electroplating solution facilitates improved filling of a Cu-Zn alloy film on an interconnect, especially for feature sizes in a dimensional range of approximately 0.2 μm to approximately 0.05 μm , thereby lowering the resistance of the formed Cu-Zn alloy film. For example, the resistance of the formed Cu-Zn alloy film can be between approximately 2.2 $\mu\Omega\cdot\text{cm}$ and approximately 2.5 $\mu\Omega\cdot\text{cm}$ for approximately 1 atom % Zn content in the Cu-Zn alloy film, as deposited. The present invention's Cu-Zn electroplating solution also provides a desirably low Zn content, e.g. in a concentration range of approximately 0.1 atomic % to approximately 1.0 atomic %, in a Cu alloy interconnect, which advantageously imparts a minimal increase in resistance as well as a substantial improvement in electromigration resistance.

Furthermore, by electroplating the Cu-Zn alloy film on a Cu surface using a stable chemical solution in prescribed concentration ranges, the present invention

advantageously achieves improved Cu interconnect reliability, improved corrosion resistance, and reduced manufacturing costs.

In contrast to the present invention as defined by amended independent claim 1, Alling does not teach, disclose, or suggest electroplating a copper (Cu) surface in a chemical solution, thereby forming a copper-zinc (Cu-Zn) alloy film on the Cu surface, “wherein the Cu-Zn alloy film has a zinc (Zn) content in a concentration range of approximately 0.10 atomic % to approximately 1.0 atomic %.” Alling specifically discloses electroplating a second metal layer, e.g. zinc and copper alloy, over a first metal layer, e.g. copper, where the second metal layer is substantially less conductive than the first metal layer. See, for example, Alling, page 2, paragraph [0022] and page 3 paragraphs [0028] and [0029]. In Alling, the preferred resistivity of the second metal layer is at least about 20 to 400 or 500 percent greater than the resistivity of the first electrically conductive (metal) layer, e.g. copper layer. See, for example, Alling, page 3, paragraph [0028]. Thus, in contrast to the present invention as discussed above, Alling is directed to electroplating a second metal layer, e.g. zinc and copper alloy, over a first metal layer, e.g. copper, where the second metal layer has substantially greater resistivity than the first metal layer.

Furthermore, Alling fails to teach, disclose, or suggest electroplating a copper-zinc (Cu-Zn) alloy film on a Cu surface, where the Cu-Zn alloy film has a zinc (Zn) content in a concentration range of approximately 0.10 atomic % to approximately 1.0 atomic %, which enables the present invention to achieve advantages discussed above. In fact,

Alling fails to teach, disclose, or suggest any particular concentration of Zn in a Cu-Zn alloy film.

In contrast to the present invention as defined by amended independent claim 1, Mahneke does not teach, disclose, or suggest electroplating a copper (Cu) surface in a chemical solution, thereby forming a copper-zinc (Cu-Zn) alloy film on the Cu surface, “wherein the Cu-Zn alloy film has a zinc (Zn) content in a concentration range of approximately 0.10 atomic % to approximately 1.0 atomic %.” The Examiner relies on Mahneke for providing motivation to enable the formation of the copper-zinc alloy film of Alling to be performed and obtain further advantage of preventing contamination on both surfaces of the wafer. Mahneke specifically discloses an electroplating chamber having a rotatable chuck, i.e. chuck 44, which allows plating, rinsing, and drying steps of an electroplating process to be performed in the same chamber. See, for example, Mahneke, column 2, lines 28-38 and column 5, lines 6-7. However, Mahneke fails to teach, disclose, or suggest, an electroplated Cu-Zn alloy film having a zinc (Zn) content in a concentration range of approximately 0.10 atomic % to approximately 1.0 atomic %. Thus, Mahneke fails to overcome the deficiencies of Alling discussed above.

In contrast to the present invention as defined by amended independent claim 1, Kowalski does not teach, disclose, or suggest electroplating a copper (Cu) surface in a chemical solution, thereby forming a copper-zinc (Cu-Zn) alloy film on the Cu surface, “wherein the Cu-Zn alloy film has a zinc (Zn) content in a concentration range of approximately 0.10 atomic % to approximately 1.0 atomic %.” The Examiner relies on

Kowalski to provide the motivation to enable the step of admixing the chemical solution with a volume of water in the combination process to be performed. However, Kowalski fails to teach, disclose, or suggest, an electroplated Cu-Zn alloy film having a zinc (Zn) content in a concentration range of approximately 0.10 atomic % to approximately 1.0 atomic %. Thus, Kowalski fails to overcome the deficiencies of Alling discussed above.

In contrast to the present invention as defined by amended independent claim 1, Krishnamoorthy does not teach, disclose, or suggest electroplating a copper (Cu) surface in a chemical solution, thereby forming a copper-zinc (Cu-Zn) alloy film on the Cu surface, “wherein the Cu-Zn alloy film has a zinc (Zn) content in a concentration range of approximately 0.10 atomic % to approximately 1.0 atomic %.” The Examiner relies on Krishnamoorthy to provide the motivation to enable the formation of the chemical solution of the combination process to be performed and obtain further advantage of solving the diffusion and self-passivation problems in metallization structure. Krishnamoorthy specifically discloses copper-zinc alloy layer 40 having a more preferable zinc content below about 2 atomic percent. See, for example, Krishnamoorthy, column 5, lines 27-28. Krishnamoorthy states that the zinc content should be chosen to balance the resistivity of the layer against the oxidation resistance and copper-confinement properties. See, for example, Krishnamoorthy, column 5, lines 38-40. However, Krishnamoorthy fails to teach, disclose, or suggest, an electroplated Cu-Zn alloy film having a zinc (Zn) content in a concentration range of approximately 0.10 atomic % to approximately 1.0 atomic %.

For the foregoing reasons, Applicant respectfully submits that the present invention, as defined by amended independent claim 1, is not suggested, disclosed, or taught by Alling, Mahneke, Kowalski, and Krishnamoorthy, either singly or in combination thereof. As such, the present invention, as defined by amended independent claim 1, is patentably distinguishable over Alling, Mahneke, Kowalski, and Krishnamoorthy. Thus claims 2-10, 21, 22, 25-28, and 30 depending from amended independent claim 1 are, *a fortiori*, also patentably distinguishable over Alling, Mahneke, Kowalski, and Krishnamoorthy for at least the reasons presented above and also for additional limitations contained in each dependent claim.

The Examiner has further rejected claim 23 under 35 USC §103(a) as being unpatentable over Alling in combination with Mahneke, Kowalski, and Krishnamoorthy, and further in view of U.S. patent number 6,309,524 B1 to Woodruff et al. Applicant has canceled claim 23.


The Examiner has further rejected claim 29 under 35 USC §103(a) as being unpatentable over Alling in combination with Mahneke, Kowalski, and Krishnamoorthy, and further in view of U.S. patent number 3,919,056 to Edward Paul Habulak. As discussed above, amended independent claim 1 is patentably distinguishable over Alling in combination with Mahneke, Kowalski, and Krishnamoorthy and, as such, claim 29 depending from amended independent claim 1 are, *a fortiori*, also patentably distinguishable over Alling in combination with Mahneke, Kowalski, and

Krishnamoorthy for at least the reasons presented above and also for additional limitations contained in dependent claim 29.

Based on the foregoing reasons, the present invention, as defined by amended independent claim 1 and claims depending therefrom, is patentably distinguishable over the art cited by the Examiner. Thus, claims 1-10, 21-22, and 25-30 pending in the present application are patentably distinguishable over the art cited by the Examiner. As such, and for all the foregoing reasons, an early allowance of claims 1-10, 21-22, and 25-30 pending in the present application is respectfully requested.

Respectfully Submitted,
FARJAMI & FARJAMI LLP

Date: 12/16/03

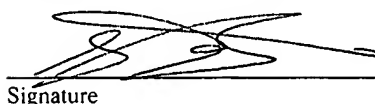

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